

ABSTRACT OF THE DISCLOSURE

The present invention provides a particle-measuring system and the particle measuring method that is provided in a processing system for generating an atmosphere including atmospheric air or a gas exhausted from within a processing chamber by a vacuum pump, and for processing a wafer W relating to a semiconductor manufacturing in this atmosphere, and that is installed on an exhaust pipe connecting between an exhaust opening of the processing chamber and the vacuum pump, for measuring the number of particles included in the exhaust gas.

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